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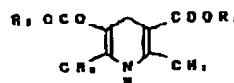
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(54) POLYVINYL CHLORIDE RESIN COMPOSITION

(57) Abstract:

PURPOSE: To obtain the titled composition durable to severe hot processing without using a metal-containing stabilizer and suitable as various materials for semiconductor industry, by compounding a polyhydric alcohol in combination with a nitrogen-containing carboxylic acid ester compound to polyvinyl chloride.

CONSTITUTION: The objective composition having a metal content of ≤ 50 ppm, preferably ≤ 20 ppm can be produced by compounding 100pts.(wt.) of polyvinyl chloride with (A) 0.01W10pts., preferably 0.1W3pts. of one or more 3-valent polyhydric alcohol compounds (e.g. trimethylethane) and (B) 0.01W10pts., preferably 0.05W3pts. of one or more nitrogen-containing compounds of formula I or II [n is 1W4; m is 0W3; m+n is 1W4; R₁ is residue of (m+n)-hydric alcohol; R₂ is alkyl].



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